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10/519,242 12/22/2004 Yasushi Akiyama 26289 7590 08/26/2005 AZ ELECTRONIC MATERIALS USA CORP.	2002JP311 EXAMI	
AZ ELECTRONIC MATERIALS USA CORP.		
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	WU, IVES J	
ATTENTION: INDUSTRIAL PROPERTY DEPT. 70 MEISTER AVENUE	ART UNIT	PAPER NUMBER
SOMERVILLE, NJ 08876	1713	

DATE MAILED: 08/26/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

·····	Application No.	Applicant(s)		
	10/519,242	AKIYAMA ET AL.		
Office Action Summary	Examiner	Art Unit		
	Ives Wu	1713		
The MAILING DATE of this communication app Period for Reply				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statup period w Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tim r within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).		
Status				
1) Responsive to communication(s) filed on 22 Dec 2a) This action is FINAL . 2b) This 3) Since this application is in condition for allowar closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro			
Disposition of Claims				
4) ⊠ Claim(s) 1-6 is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5) □ Claim(s) is/are allowed. 6) ⊠ Claim(s) 1-6 is/are rejected. 7) □ Claim(s) is/are objected to. 8) □ Claim(s) are subject to restriction and/o				
Application Papers		•		
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) accomplicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Example 11.	epted or b) objected to by the I drawing(s) be held in abeyance. Sec ion is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).		
Priority under 35 U.S.C. § 119				
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document: 2. Certified copies of the priority document: 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stage		
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Do 5) Notice of Informal F 6) Other:			

U.S. Patent and Trademark Office PTOL-326 (Rev. 1-04)

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DETAILED ACTION

Claim Rejections - 35 USC § 102/103

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:

- 1. Determining the scope and contents of the prior art.
- 2. Ascertaining the differences between the prior art and the claims at issue.
- 3. Resolving the level of ordinary skill in the pertinent art.
- 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

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(1). Claims 1-6 are rejected under 35 U.S.C. 102(b) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Mineo et al (JP 08-044066, machine-translated).

Mineo et al disclose a surface antireflection coating compound containing water-soluble fluorine compound, water, ammonium salts, and alkyl carboxylic acid.

As to the components of a fluorine-containing polymer, an acid, an amine and aqueous solvent in an antireflective coating composition in **the independent claim 1**, Mineo et al disclose that the patentee's invention includes a water-soluable fluorine compound and water, [0011], line 8-9, a fluorination alkyl polyether carboxylic acid, [0011], line 7, as a nonmetallic ammonium salt, [0016], line 4. It is 2% or more still more preferably 1% or more preferably to total constituent weight, and is 5% or less. The polyvinyl alcohol and polyacrylic acid which are generally known, [0013], line 1-3.

As to the pH value of less than 7 in the anti-reflective coating composition in **the independent claim 1**, in view of the fact that Mineo et al disclose the fluorinated compound containing acid groups of polymers such as fluorination alkyl polyether carboxylic acid, fluorination alkyl polyether sulfonic acid and other acids used for surface acid-resisting spreading constituents to obtain the desirable refractive index between 1.27 to 1.3, [0008], line 1-2, it is therefore the examiner's position to believe that the anti-reflective coating composition compound of patentee's would inherently possess the pH value 7 or less. Since USPTO does not have proper means to conduct the experiments, it is now shift the burden to the applicant to prove otherwise, *In re Fitzgerald, 205 USPQ 594 (CCPA 1980)*

As to the limitation of **dependent claim 2**, Mineo et al disclose florination alkyl polyether carboxlic acid and fluorination alkyl polyether sulfonic acid, [0011]. Furthermore, Mineo et al disclose the formula of fluorination alkyl polyether sulfonic acid as following:

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$$[(CF_2CF_2)_n - CF-CF_2]_x$$

| $(O-CF_2CF(CF_3))_m - OCF_2CF_2SO_3H$ [0040].

Although Mineo et al do not disclose the formula for fluorination alkyl polyether carboxylic acid, based on the formula of fluorination alkyl polyether sulfonic acid disclosed by

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Mineo et al, and general formulas disclosed for polyether sulfonic group and polyether carboxylic group in [0014], it is reasonable to believe that the fluorination alkyl polyether carboxylic acid will have the similar formula:

which meets the structure of general formula (I) or both (I) and (II) of applicant's instant claim 2.

As to the limitation of **dependent claim 3**, Mineo et al disclose polyacrylic acid, [0013], line 3.

As to the limitation of **dependent claim 4**, Mineo et al disclose tetramethylammonium hydroxide, [0036], line 5.

As to the limitation of **dependent claim 5**, Mineo et al disclose water, [0011], line 9.

As to the limitation of **dependent claim 6**, Mineo et al disclose the method of exposing the photoresist coating wafer with the surface acid-resisting spreading film through a **test pattern** using g line stepper (GCA co. make; DSW-6700B) and performing for [PEB] 90 seconds at **120 degrees C on a hot plate**, the development omission **pattern** of 10-micrometer angle in light exposure and the 1-micrometer Rhine and tooth-space pattern with which the 1-micrometer Rhine and tooth space is finished in 1:1 were observed with the scanning electron microscope. [0043], line 1-6.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ives Wu whose telephone number is 571-272-4245. The examiner can normally be reached on 8:00 - 5:00.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Wu can be reached on 571-272-1114. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Examiner: Ives Wu

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Date: August 22,2005

DAVID W. WU
SUPERVISORY PATENT EXAMINER
OF CENTER 1700